Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4728	((216/41,51,95-97,99) or (438/735,736,745,753,756,757)). CCLS.	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L3	88721	(si OR silicon\$4) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L4	15035	L3 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L5	824	L4 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L6	385	L5 AND (stress\$4 OR strain\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L7	158	L6 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L8	101	L7 AND (anisotropic\$4 NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L9	3	L1 AND L8	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L10	11963	(si OR silicon\$4) NEAR20 etch\$4 NEAR20 wet\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L11	8266	L10 AND (etch\$4 NEAR20 mask\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L12	3286	L11 AND ((etch\$4 NEAR20 mask\$4) NEAR20 nitride\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:51
L13	2274	L12 AND ((etch\$4 NEAR20 mask\$4) NEAR20 oxide\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:51
L14	243	L13 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:51
L15	28	L1 AND L14	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L16	1714	(si OR silicon\$4) NEAR20 etch\$4 NEAR20 wet\$4	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:50
L17	475	L16 AND (etch\$4 NEAR20 mask\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:51
L18	121	L17 AND ((etch\$4 NEAR20 mask\$4) NEAR20 nitride\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:51
L19	76	L18 AND ((etch\$4 NEAR20 mask\$4) NEAR20 oxide\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:52

L20	1	L19 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:52
S5	88438	(si OR silicon\$4) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:04
S18	14996	S5 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:43
S21	822	S18 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:06
S22	2	S21 AND (nitrid\$4 NEAR20 (stress\$4 OR strain\$4) NEAR20 relax\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 09:15
S23	20	S21 AND ( (stress\$4 OR strain\$4) NEAR20 relax\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 14:59
S24	6716	((silicon OR Si) NEAR20 etch\$4) AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 15:09
S25	822	S24 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 15:10
S26	385	S25 AND (stress\$4 OR strain\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 16:40
S27	145	S26 AND ((stress\$4 OR strain\$4) NEAR20 (reduc\$5 OR relief\$4 OR relax\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/21 16:18
S28	347	S25 AND ((stress\$4 OR strain\$4) NEAR20 crack\$4 OR defect\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 16:48
S29	30	S25 AND ((stress\$4 OR strain\$4) NEAR20 crack\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 17:02
S30	88721	(si OR silicon\$4) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2005/11/29 09:15
S31	15035	S30 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 09:15
S32	824	S31 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:53
S33	122	S32 AND (nitrid\$4 NEAR20 (stress\$4 OR strain\$4))	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:18
S34	42	S33 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:18
S35	4	S34 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6) NEAR20 (groove\$4 OR trench\$4 OR open\$4))	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:59

S36	50	(("5616401") or ("6057241") or ("6720226") or ("4925807") or ("6174792") or ("6908858") or	USPAT	OR	OFF	2005/11/29 10:53
		("4951063") or ("5240559") or ("5275695") or ("5348906") or				
		("5604371") or ("5665641") or				
		("5754619") or ("5905005") or				
		("5920780") or ("5999590") or ("6004840") or ("6081308") or				
		("6128363") or ("4371407") or				
		("4445967") or ("4839708") or ("5204210") or ("5259924") or	<u> </u>			
		("5291536") or ("5358893") or				
		("5362350") or ("5362575") or				
		("5364743") or ("5382823") or ("5395802") or ("5420079") or				
		("5498566") or ("5506168") or				
		("5512509") or ("5539256") or ("5541023") or ("5599722") or				
		("5627099") or ("5677229") or				
		("5677090") or ("5789769") or				
		("5804504") or ("5818109") or ("5821402") or ("5848120") or				
		("5905044") or ("6013573") or				
		("6037083") or ("6121110")).PN.				
S37	0	S33 AND S36	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:53
S38	1	S32 AND S36	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:53
S39	385	S32 AND (stress\$4 OR strain\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:18
S40	158	S39 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:22
S41	101	S40 AND (anisotropic\$4 NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:23
S42	1	("5738757").PN.	USPAT	OR	OFF	2005/11/30 08:53
S43	11963	(si OR silicon\$4) NEAR20 etch\$4 NEAR20 wet\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:05
S44	8266	S43 AND (etch\$4 NEAR20 mask\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:05
S45	4865	S44 AND ((etch\$4 NEAR20	US-PGPUB;	OR	OFF	2005/11/30 09:06
		mask\$4) NEAR20 (nitride\$4 OR oxide\$4))	USPAT			
S46	704	S45 AND ((hydroxide\$4 OR	US-PGPUB;	OR	OFF	2005/11/30 09:07
310	/07	alkali\$4) NEAR20 etch\$4)	USPAT		011	2003/11/30 03.0/
S47	3286	S44 AND ((etch\$4 NEAR20	US-PGPUB;	OR	OFF	2005/11/30 09:07
		mask\$4) NEAR20 nitride\$4)	USPAT			
S48	2274	S47 AND ((etch\$4 NEAR20 mask\$4) NEAR20 oxide\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:07

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C:\Documents and Settings\echen\My Documents\EAST\Workspaces\Anisotropic Wet Etching of Silicon.wsp

S49	243	S48 AND ((hydroxide\$4 OR	US-PGPUB;	OR	OFF	2005/11/30 09:07
		alkali\$4) NEAR20 etch\$4)	USPAT			
***********	17	("5738757").URPN.	USPAT	OR	OFF	2005/11/30 09:28